

CLAIMS

1. A method for use in fabricating a chip, the method comprising the steps of:

determining a density and location of at least one functional area of a layer; and

adding dummy structures to said layer as a function of the determined density and determined location.

2. The method of claim 1 wherein for at least one of the dummy structures, the adding step includes the steps of:

determining a placement of said one dummy structure as a function of the width and density of functional areas within a predetermined distance of a location; and

determining a size of said one dummy structure as a function of the determined placement.

3. The method of claim 2 further comprising determining a shape of said one dummy structure as a function of the determined size.

4. A method for use in fabricating a chip, the method comprising the steps of:

determining a density and location of functional areas of a layer in relation to a location being processed; and

adding dummy structures to said layer as a function of the determined density and determined location, said dummy structures each having placement determined as a function of the width and density of the functional areas, size determined as a function of the

determined placement, and shape determined as a function of the determined size.